



CAV 2813\$

11/CPA
J. Dawkins
4/21/99

**CONTINUED PROSECUTION APPLICATION (CPA)
UNDER 37 C.F.R. § 1.53(d)
REQUEST TRANSMITTAL**

Address to: Assistant Commissioner for Patents Box CPA Washington, D.C. 20231	Attorney Docket No.:	303.573US1
	First Named Inventor:	Gurtej Singh Sandhu
	Express Mail No.:	EL254620657US
	Total Pages (if by fax):	

This is a request for filing a continuation application under 37 CFR § 1.53(d) of prior application Serial No. 08/636,069, filed on April 22, 1996, entitled METHOD TO REDUCE FIXED CHARGE IN CVD OZONE DEPOSITED FILMS.

The above-identified prior application in which no abandonment of, or termination of, proceedings has occurred, is hereby expressly abandoned as of the filing date of this request for a CPA. Please use all the contents of the prior application file wrapper, including the drawings, as the basic papers for the new application. (37 CFR 1.53(b) must be used for continuation-in-part applications or for applications where the prior application is not to be abandoned.)

1. ☐ Enter the amendment previously filed on ☐ under 37 CFR 1.116, but unentered, in the prior application.
2. ☒ A Preliminary Amendment (14 pages) is enclosed.
3. ☐ This application is filed by fewer than all the inventors named in the prior application, 37 CFR 1.53(d)(4).
 - a. ☐ **DELETE** the following inventor(s) named in the prior nonprovisional application:

 - b. ☐ The inventor(s) to be deleted are set forth on a separate sheet attached hereto.
4. ☐ A new power of attorney is enclosed.
5. ☐ Information Disclosure Statement is enclosed.
 - a. ☐ Form(s) 1449
 - b. ☐ Copies of IDS Citations

04/19/1999 SLUANG1 00000004 08636069

01 FC:131	760.00 OP
02 FC:102	702.00 OP
03 FC:103	234.00 OP
04 FC:117	670.00 OP

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The filing fee is calculated below on the basis of the claims existing in the prior application as amended at 1 and 2 on the previous page:

	No. Filed	No. Extra	Rate	Fee
TOTAL CLAIMS	33 - 20 =	13	x 18 =	\$234.00
INDEPENDENT CLAIMS	12 - 3 =	9	x 78 =	\$702.00
[] MULTIPLE DEPENDENT CLAIMS PRESENTED				\$0.00
BASIC FEE				\$760.00
TOTAL				\$1,696.00

6. ☐ Small Entity Status:

- a. ☐ A small entity statement is enclosed.
b. ☐ A small entity statement was filed in the prior nonprovisional application and such status is still proper and desired.
c. ☐ Is no longer claimed.

7. ☒ A check in the amount of \$1,696.00 is attached to pay the filing fee.

8. ☒ The Commissioner is hereby authorized to credit overpayments or charge any fees set forth in 37 CFR 1.16 through 1.18 to Deposit Account No. 19-0743.

9. ☒ A petition for extension of time in the prior application is enclosed along with a check in the amount of \$870.00 to pay the extension fee.

10. ☒ Other : A Revocation and Power of Attorney (2 pgs.)

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By: Thomas W. Leffert
Atty: Thomas W. Leffert
Reg. No. 40,697

Customer Number **21186**

"Express Mail" mailing label number EL254620657US

Date of Deposit April 15, 1999

I hereby certify that this paper or fee is being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 C.F.R. 1.10 on the date indicated above and is addressed to Box CPA, Assistant Commissioner for Patents, Washington, D. C. 20231

Chris Hammond
Printed Name

Chris Hammond
Signature

S/N 08/636,069



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Gurtej Singh Sandhu et al.

Examiner: Matthew Wipple

Serial No.: 08/636,069

Group Art Unit: 2813

Filed: April 22, 1996

Docket: 303.573US1

Title: METHOD TO REDUCE FIXED CHARGE IN CVD OZONE DEPOSITED FILMS

12/1 PRE.
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J. Dawkins
4-21-99

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Prior to examining the Continuing Prosecution Application for the above-identified patent application, please amend the application as follows:

IN THE SPECIFICATION

- ✓ On page 6, line 6, after "reaction" please remove "volume of gas, above the"
- ✓ On page 8, line 3, after "which in turn" please remove "will"

IN THE CLAIMS

- ✓ Please cancel claims 3 and 11-30 without prejudice. Please add claims 31-54

- Sub C*
1. (Amended) A chemical vapor deposition (CVD) process for depositing borophosphosilicate glass [SiO_2] films on a substrate surface, [said]the process comprising [the steps of]:
- [(a)] disposing the substrate within a chemical vapor deposition reaction chamber;
 - [(b)] introducing a gas volume of SiO_2 precursors into [said]the chamber;
 - [(c)] admitting a gas volume of ozone into the chamber;
admitting a dopant source for phosphorus into the chamber;
admitting a dopant source for boron into the chamber; and
 - [(d)] illuminating, with a source of high intensity light, the volume of gas located [within a chemically reactive distance of]above the substrate [assembly] surface[, without illuminating the substrate assembly].

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